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7/21/03
Hollish

PATENT
97-CCP-251 DIV

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
ERIC GERRITSEN, et al.)
Serial No.: 09/858,400)
Filed: May 16, 2001)
For: PROCESS FOR FORMING A LOW)
RESISTIVITY TITANIUM SILICIDE)
LAYER ON A SILICON SEMICON-)
DUCTOR SUBSTRATE (As Amended))

Group Art Unit: 2813

Examiner: T. Nguyen

AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated January 3, 2003, the due date for response to which has been extended to July 3, 2003 by the enclosed petition for extension of time, in connection with the above-identified application, please enter and consider the following amendment and remarks.

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to:
Commissioner for Patents, P.O. Box 1450,

Alexandria, VA 22313-1450, on 7/3/03
Date of Deposit

Stephen Bongini
Applicant, Assignee, or Representative

[Signature]
Signature

7/3/03
Dated

RECEIVED
JUL 16 2003
TECHNOLOGY CENTER 2800

07/21/2003
01 FL:1205